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The World's Highest Resolution Projection EUV Lithography Tool

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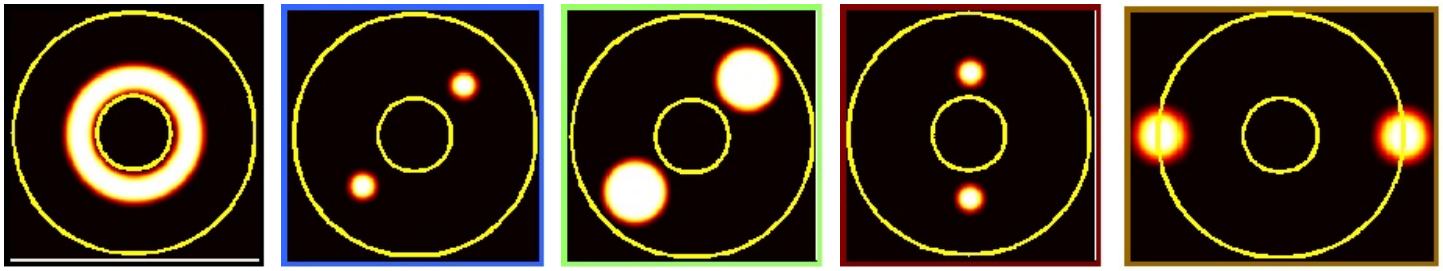
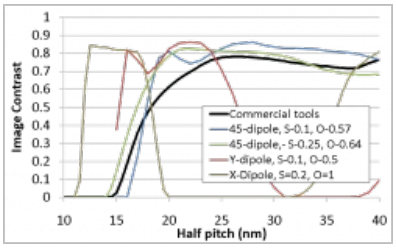
The SEMATECH-Berkeley MET achieves its world leading performance through the precise manipulation of illumination coherence. Through the use of the unique scanner module and undulator radiation from the ALS, lossless variable illumination can be achieved in patterns such as those pictured here.

Synthesized Pupil Fill Functions



45-dipole, S=0.1, O=0.57 | 45-dipole, S=0.25, O=0.64 | Y-dipole, S=0.1, O=0.5 | X-dipole, S=0.2, O=1



This coherence control has been demonstrated experimentally at the BMET, as can be seen by comparing the predicted aerial images with actual printing results: